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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/761,985	01/21/2004	Ming-Cheng Chang	10113681	4317

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QUINTERO LAW OFFICE  
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EXAMINER

TRAN, THIEN F

ART UNIT PAPER NUMBER

2811

DATE MAILED: 09/27/2006

Please find below and/or attached an Office communication concerning this application or proceeding.



## **DETAILED ACTION**

### ***Claim Rejections - 35 USC § 102***

The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless –

(b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.

Claims 19-30 are rejected under 35 U.S.C. 102(b) as being anticipated by Gruening et al. (US 6,204,140).

Gruening et al. discloses a transistor (Fig. 1), comprising a source/drain region (N+, S, 71); a buried strap out-diffusion region (N+ , D, 72) adjacent to one sidewall of a deep trench (12); and a bended gate structure having a bended gate (20) and a bended gate insulating layer (thin dielectric layer 39), wherein the bended gate structure comprises a first portion extending along a first direction and a second portion extending along a second direction intersecting with the first direction, wherein the first portion of the bended gate is adjacent to the source/drain region and the second portion of bended gate is adjacent to the buried strap out-diffusion region.

Regarding claim 20, the deep trench (12) is a trench of a deep trench capacitor.

Regarding claim 21, the bended gate is adjacent to a shallow trench isolation (STI, 28).

Regarding claim 22, a bit line contact (17) is electrically contacting the source/drain region (S).

Regarding claim 23, a spacer (19) is formed on a sidewall of the bended gate (20) between the bit line contact (17) and the bended gate (20).

Regarding claim 24, the bended gate is L shaped in a cross section view.

Regarding claim 25, the bended gate insulating layer (thin layer 39) is L shaped in a cross section view.

Regarding claim 26, the first direction and the second direction are perpendicular.

Regarding claim 27, the source/drain region (N+, S, 71) is disposed in a substrate.

Regarding claim 28, the first direction is parallel to the substrate surface.

Regarding claim 29, the second direction is parallel to a sidewall of the trench (12).

Regarding claim 30, Gruening et al. further discloses a memory device, comprising a deep trench capacitor (10) and a transistor (9) controlling the deep trench capacitor, wherein the transistor is as claimed in claim 19.

### ***Response to Arguments***

Applicant's arguments with respect to claims 19-30 have been considered but are moot in view of the new ground(s) of rejection.

### ***Conclusion***

Applicant's amendment necessitated the new ground(s) of rejection presented in this Office action. Accordingly, **THIS ACTION IS MADE FINAL**. See MPEP

§ 706.07(a). Applicant is reminded of the extension of time policy as set forth in 37 CFR 1.136(a).

A shortened statutory period for reply to this final action is set to expire THREE MONTHS from the mailing date of this action. In the event a first reply is filed within TWO MONTHS of the mailing date of this final action and the advisory action is not mailed until after the end of the THREE-MONTH shortened statutory period, then the shortened statutory period will expire on the date the advisory action is mailed, and any extension fee pursuant to 37 CFR 1.136(a) will be calculated from the mailing date of the advisory action. In no event, however, will the statutory period for reply expire later than SIX MONTHS from the date of this final action.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Thien F. Tran whose telephone number is (571) 272-1665. The examiner can normally be reached on 8:30AM - 5:00PM Monday through Friday.


If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Eddie C. Lee can be reached on (571) 272-1732. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see <http://pair-direct.uspto.gov>. Should

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you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free). If you would like assistance from a USPTO Customer Service Representative or access to the automated information system, call 800-786-9199 (IN USA OR CANADA) or 571-272-1000.

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September 21, 2006

  
Thien Tran  
Primary Examiner